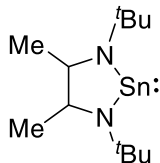


Catalog # 50-1150 N,N'-Di-t-butyl-2,3-diamidobutanetin(II), 98%



## Thermal Behavior:

- Vacuum sublimation at 40-45°C [5]
- Vapor pressure: 0.42 Torr at 40°C [1], 0.52 Torr at 45°C [5]
- TGA diagram and data is available in [3, 5]

## Technical Notes:

1. ALD precursor for tin thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
SnO <sub>x</sub>	ALD	40°C	5.5 Torr	H <sub>2</sub> O <sub>2</sub>	50-150°C	1
	ALD	40°C	2 Torr	NO	130-250°C	2
SnO	AACVD	0.1M in toluene	-	-	250-350°C	3
(Sn,Al)O <sub>x</sub>	ALD	40°C	-	H <sub>2</sub> O <sub>2</sub> ; TMA	120°C	4
SnS	ALD	45°C	-	H <sub>2</sub> S	50-200°C	5

## References:

1. [Chem. Mater. 2010, 22, 4964](#)
2. [J. Mater. Chem. 2012, 22, 4599](#)
3. [Chem. Commun. 2013, 49, 8773](#)
4. [J. Phys. Chem. C, 2011, 115, 10277](#)
5. [Chem. Mater. 2014, 26, 3065](#)